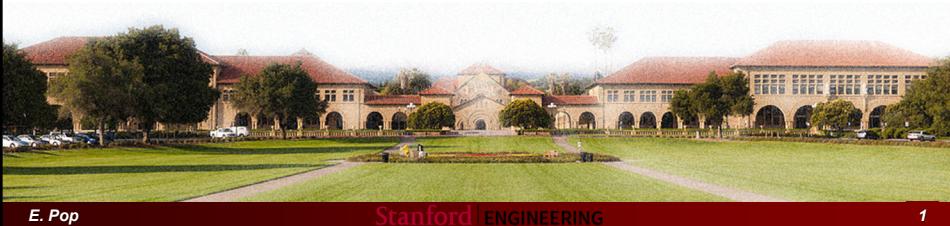


# Electronics and Energy Applications of 1D and 2D Nanomaterials

Eric Pop

Electrical Engineering (EE) and Precourt Institute for Energy (PIE)  
Stanford University

<http://poplab.stanford.edu>



E. Pop

Stanford ENGINEERING

1

## Acknowledgements

<http://poplab.stanford.edu>

- **Alumni:**

- Prof. D. Estrada, Drs. Z.-Y. Ong, A. Liao, J. Wood, Z. Li, V. Dorgan, F. Xiong, Z. Li, E. Carrion, S. Islam, K. Grosse
- 8 M.S. and 10 B.S. theses

- **Post-docs:**

- Feng Xiong, Yong Cheol Shin, Eilam Yalon, Miguel Munoz

- **Grad students:**

- C. English, F. Lian, S. Deshmukh, S. Bohaichuk
- M. Mleczko, C. Neumann, I. Datye, M. Chen, A. Gabourie
- K. Smithe, S. Suryavanshi, N. Wang, R.L. Xu, C. McClellan

- **Undergrads:**

- Andrew, Tim, Job, Justin, Yeshar, Erin

- **Sponsors:**

- National Science Foundation (NSF), Army Research Office (ARO)
- Air Force (AFOSR), Intel, STARnet-SONIC, **SystemX Alliance**

- **Collaborators:**

- Z. Bao, K. Goodson, S. Mitra, Y. Nishi, E. Reed, K. Saraswat, H.-S.P. Wong (Stanford), D. Cahill, W. King, J. Lyding, J. Rogers, M. Shim (UIUC), M. Rudan (Bologna), C. Jacoboni (Modena), M. Hersam (NWU), I. Knezevic (Wisc.), D. Jena (Cornell), D. Ielmini, R. Sordan (Milano), J. Shiomi (Tokyo)



E. Pop

Stanford ENGINEERING

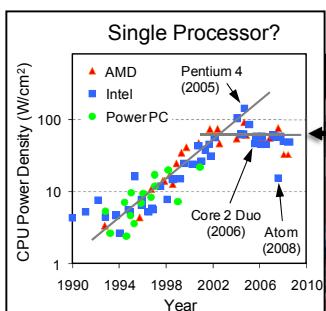
2

## What Motivates Us



(conventional Moore's Law size scaling can get us ~10x)

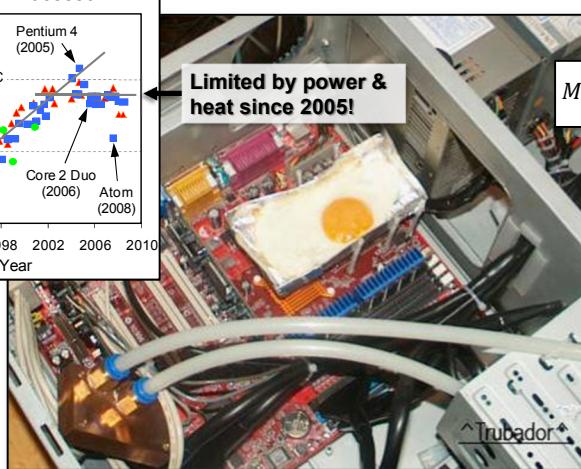
## Electronics Use (and Waste) Much Power



E. Pop, *Nano Research* 3, 147 (2010)  
new course: Energy in Electronics, EE 323 (Fall 2014)

Limited by power & heat since 2005!

$$MTF \sim \exp\left(\frac{E_A}{k_B T}\right)$$



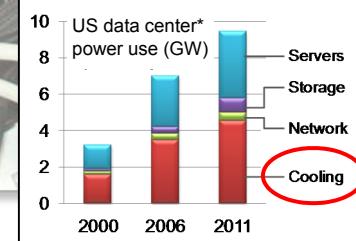
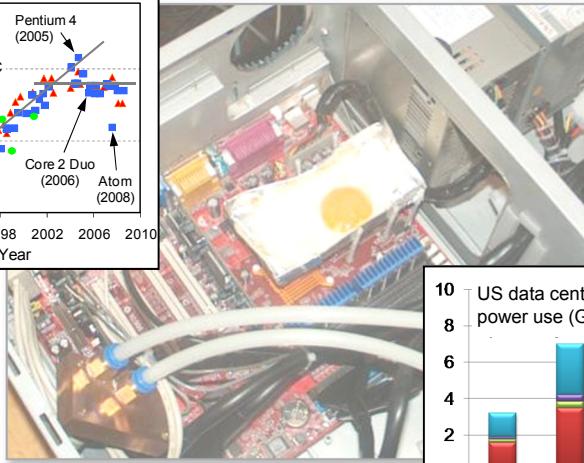
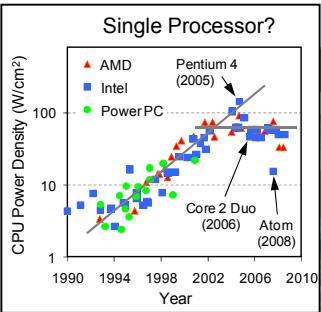
[http://phys.ncku.edu.tw/~htsu/humor/fry\\_egg.html](http://phys.ncku.edu.tw/~htsu/humor/fry_egg.html)

energy limits performance from processors, to mobile devices, to data centers

## Electronics Use (and Waste) Much Power

E. Pop, *Nano Research* 3, 147 (2010)

new course: Energy in Electronics, EE 323 (Fall 2014)



Calibrating: 1 GW ~ 1 nuclear power plant  
12 GW ~ all electricity used by Argentina

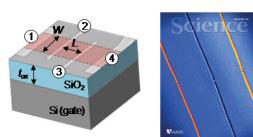
\*World-Wide about 30 GW

E. Pop

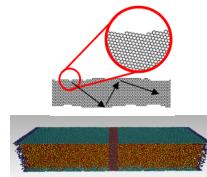
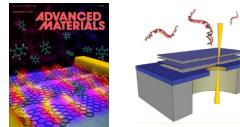
Stanford ENGINEERING

5

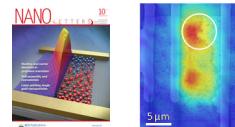
## Our Work: Two Sides of the Same Coin



**Lower power at its source**  
(devices, sensors, circuits)



**Harvest and manage heat**  
(energy, thermoelectrics)



**fundamental understanding**  
**practical applications**

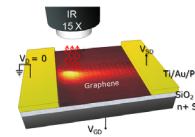
E. Pop

Stanford ENGINEERING

6

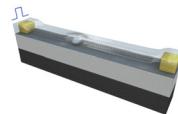
## Outline of Talk

- The SystemX Alliance at Stanford



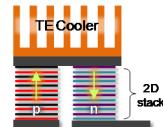
- Transistors

- Heterogeneous integration of beyond-Si materials



- Data Storage

- Approaching limits of phase-change memory



- Thermal Energy at Nanoscale

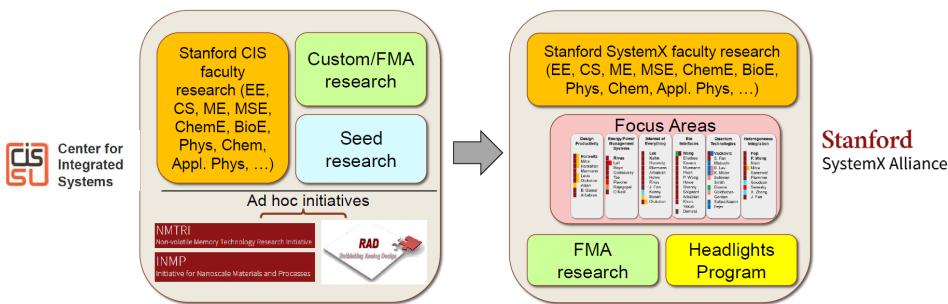
- Ballistic heat flow and fundamental limits

# What Is the SystemX Alliance at Stanford?

- Center for Integrated Systems (CIS) → SystemX Alliance

- Industry-academic Alliance to repositioned for 21st century research

- Become “the” hub for electronic research at Stanford



- What's New?

- Stronger emphasis of top-down, **systems research**

- Introduce **focus areas** to create coherent thrusts

- Additional **sponsor benefits** including workshops, E-Seminars

## Value Proposition for Industry Sponsors

- See **everything** that is going on at Stanford
  - Real-time **view of all faculty research**, including NSF, DARPA, etc. activities
  - **Student** recruiting, internships, and networking
- Participation in Focus Area research
  - Invitation-only attendance to **bi-annual workshop** & discussion
- Customized Fellow-Mentor-Advisor (FMA) projects
  - **Company-specific research** performed by student & advisor with industry mentor
- Faculty liaisons, company visits, and weekly **E-Seminars**

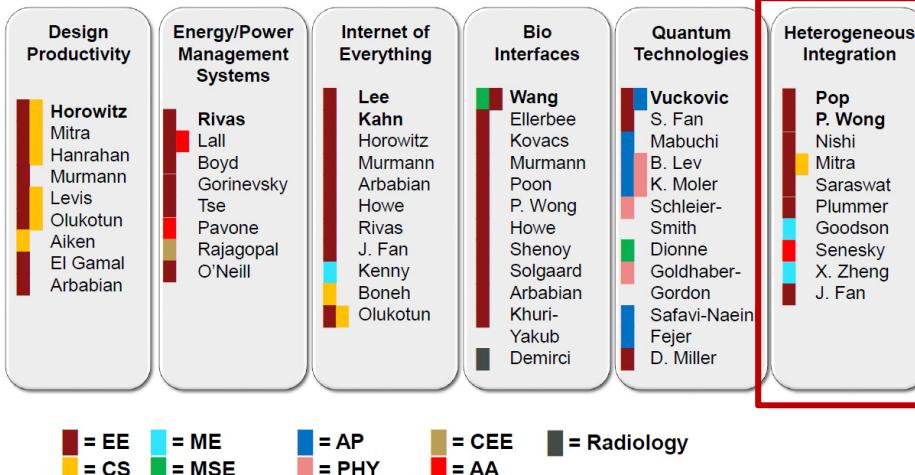


E. Pop

Stanford ENGINEERING

9

## SystemX Focus Areas



- Focus areas change dynamically and have finite life-cycle (~3-5 years)

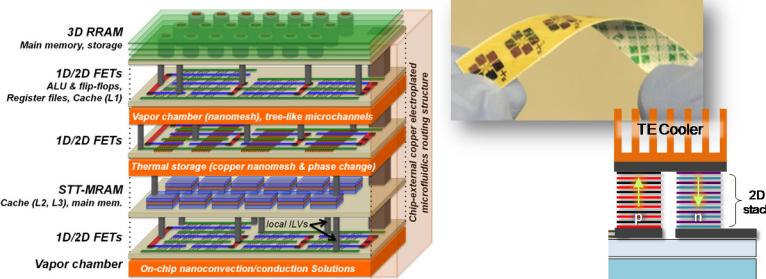
E. Pop

Stanford ENGINEERING

10

## Heterogeneous Integration Focus Area

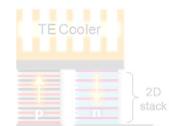
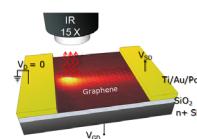
- Heterogeneous Integration of Everything onto Anything (HIEA)
- Integration of “beyond-Si” platforms for “beyond Moore” applications
  - Monolithic integration of logic, memory, sensors, thermal management, flexible substrates
  - Energy-efficient and brain-inspired design opportunities
  - Autonomous electronics and energy-harvesting opportunities



- Core faculty: E. Pop, H.-S.P. Wong (co-leads), J. Fan, K. Goodson, S. Mitra, Y. Nishi, J. Plummer, K. Saraswat, D. Senesky, X. Zheng

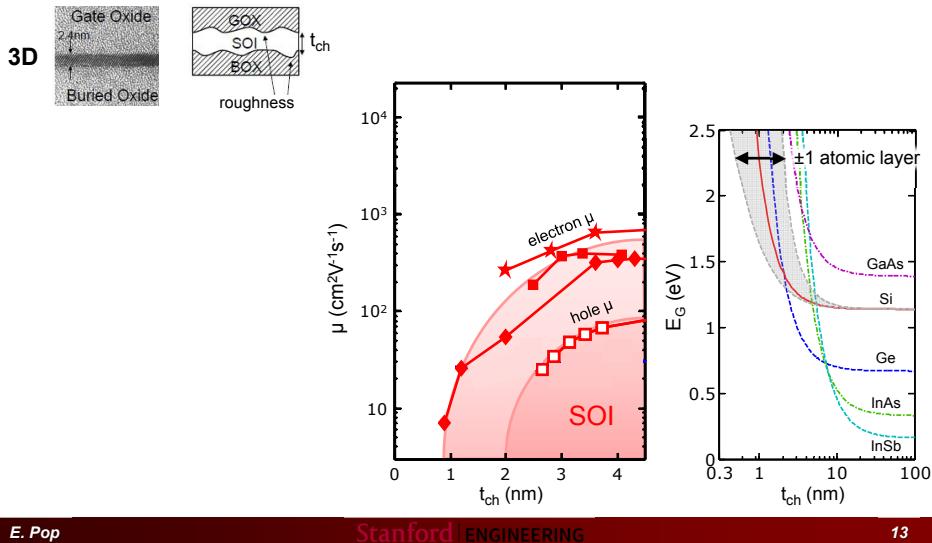
## Outline of Talk

- The SystemX Alliance at Stanford
- Transistors
  - Integration of electronics based on 2D materials
- Data Storage
  - Approaching limits of phase-change memory
- Thermal Energy at Nanoscale
  - Ballistic heat flow and fundamental limits



## Transistors Beyond Silicon?

- Problem: 20<sup>th</sup> century transistors “carved” out of 3D materials (Si) → surface roughness restricts mobility, band gap, variability



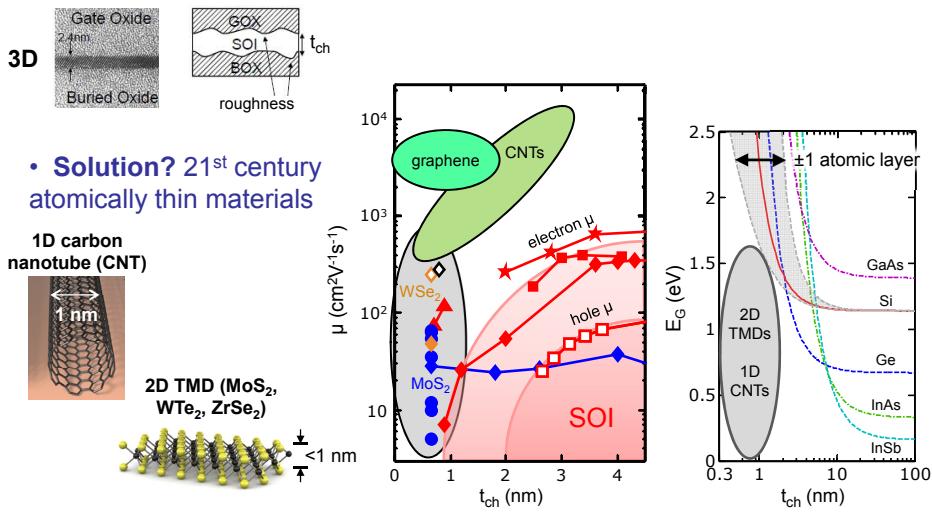
E. Pop

Stanford ENGINEERING

13

## Transistors Beyond Silicon?

- Problem: 20<sup>th</sup> century transistors “carved” out of 3D materials (Si) → surface roughness restricts mobility, band gap, variability



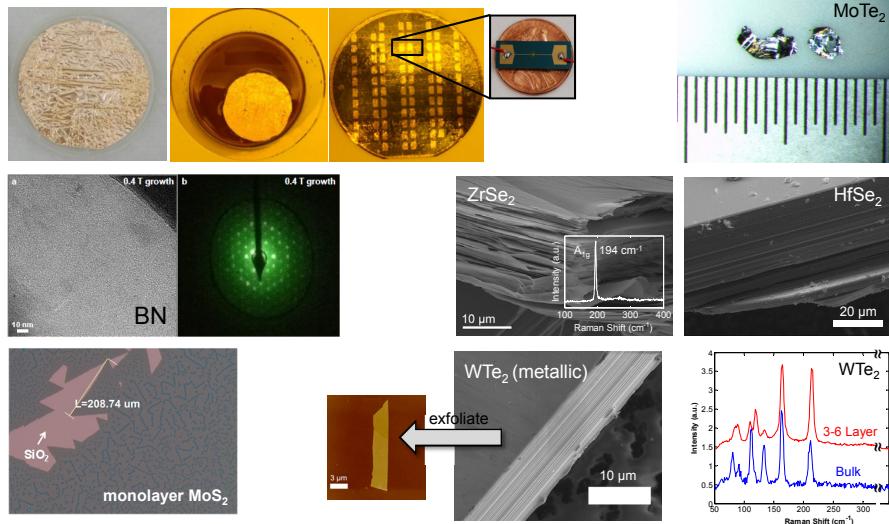
E. Pop

Stanford ENGINEERING

14

## Beyond-Silicon 2D Materials

### CVD growth of graphene, BN and MoS<sub>2</sub>



collab. H.S.-P. Wong, Y. Nishi, I. Fisher

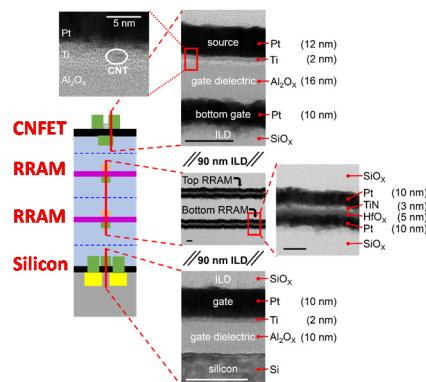
### CVT growth of MoTe<sub>2</sub>, WTe<sub>2</sub>, ZrSe<sub>2</sub>, HfSe<sub>2</sub>

E. Pop

Stanford ENGINEERING

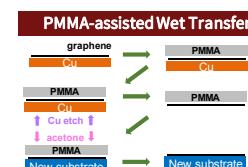
15

## Heterogeneous Integration Progress



**Monolithic 3D:** low-temperature 3D integration of CNT logic and RRAM memory on CMOS substrate

source: Shulaker, Wong, Mitra (IEDM-2014)



**Wet or Dry Transfer:** layer transfer of 2D monolayers onto insulators while preserving the electronic properties

source: K. Smithe (Pop Lab, 2015)

E. Pop

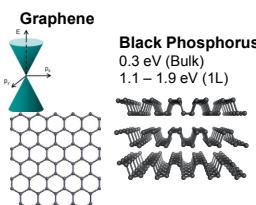
Stanford ENGINEERING

16

## Band Gaps ( $E_G$ ) of Several 2D Materials

courtesy of M. Mleczko (Pop Lab)

### High-Speed / RF



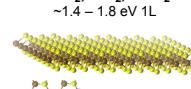
**Low-Power CMOS**  
~0.5–1.2 eV

Ge 0.67 eV

Si 1.11 eV

WSe<sub>2</sub>, WS<sub>2</sub>, MoS<sub>2</sub>

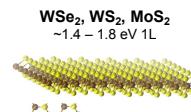
~1.4 – 1.8 eV 1L



Layered Insulators

h-BN

### Power Devices



$E_G$  0 eV

1 eV

2 eV

- Low- $E_G$  but high mobility → high-speed and RF applications
- Medium- $E_G$  (0.3 to 1.1 eV) → low-power CMOS
- High- $E_G$  → power devices

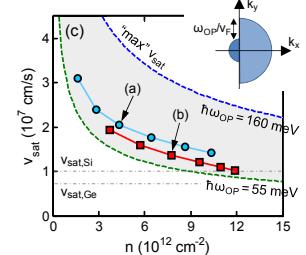
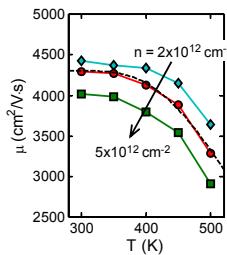
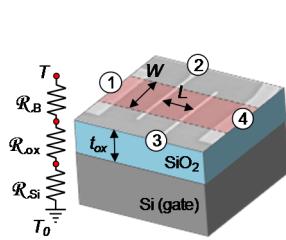
E. Pop

Stanford ENGINEERING

17

## Early Work: Graphene Transport Parameters

V. Dorgan, M.-H. Bae, E. Pop, *Appl. Phys. Lett.* 97, 082112 (2010)



$$\Delta T = T - T_0 \approx P(\mathcal{R}_B + \mathcal{R}_{ox} + \mathcal{R}_{Si})$$

$$\mu(n, T) = \frac{\mu_0}{1 + (n/n_{ref})^\alpha} \times \frac{1}{1 + (T/T_{ref} - 1)^\beta}$$

$$v_{sat}(n, T) = \frac{2}{\pi} \frac{\omega_{OP}}{\sqrt{\pi n}} \sqrt{1 - \frac{\omega_{OP}^2}{4\pi n v_F^2}} \frac{1}{N_{OP} + 1}$$

- Lack of transport data\* at  $T > 300$  K and high-field  $v_{sat}$  ( $> 1$  V/ $\mu$ m)
- High-field  $v_{sat}$  measurement is tricky, needs constant field
- Also extracted practical electrical and thermal compact models

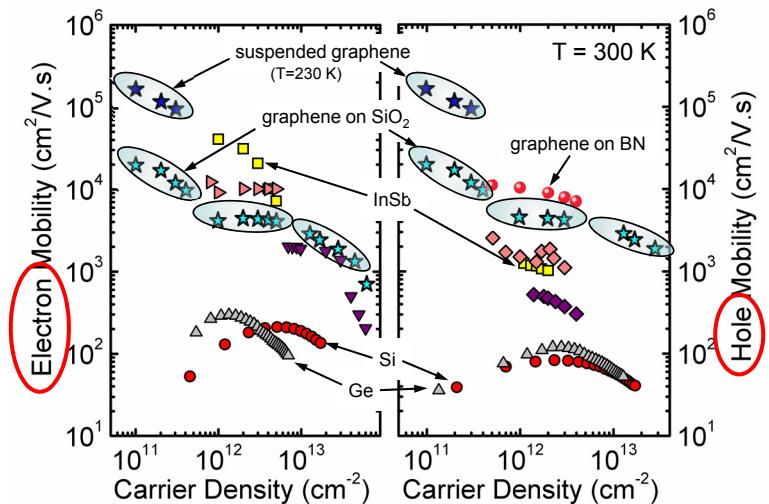
\*J.-H. Chen, *Nature Nano* (2008); W. Zhu, *PRB* (2009); I. Meric, *Nature Nano* (2008)

E. Pop

Stanford ENGINEERING

18

## Graphene Mobility – Where Does it Stand?

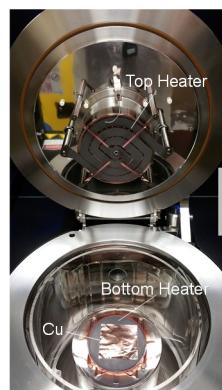


mobility = characterizes “ease” of current flow in a material; e.g.  $I \propto n\mu E$

## Today: Graphene-Based Functions and Systems

- Goal: graphene switched analog circuit (SAC). Why?
- Graphene = nanofabrics with high mobility ( $\sim 10x > \text{Si}$ ), flexible...
- SAC tolerates low  $I_{\text{on}}/I_{\text{off}}$  ratio ( $\sim 5x$ ) of graphene (no band gap)
- Breakthroughs in heterogeneous integration of graphene & CMOS

4" Aixtron  
Black Magic  
System

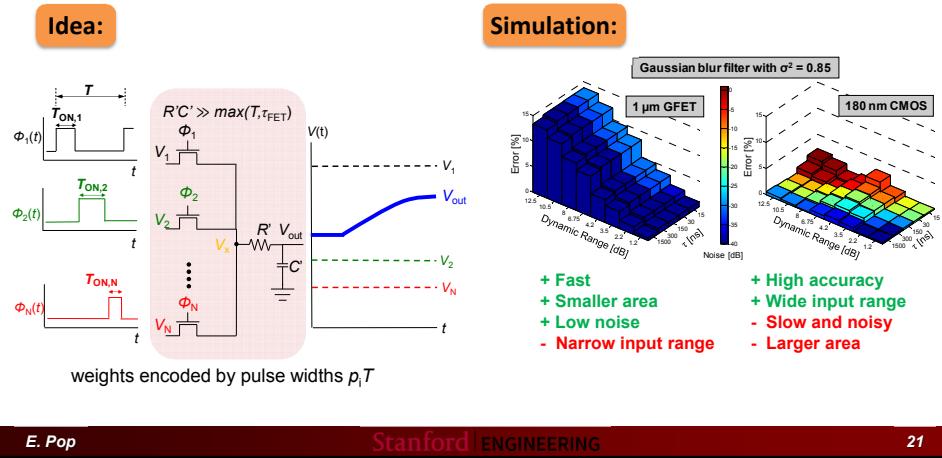


Growth  
Chamber

# Graphene Dot Product (GDOT) Nanofunction

N. Wang, S. Gonugondla, I. Nahlus, N. Shanbhag, E. Pop, VLSI Symp. (2016)

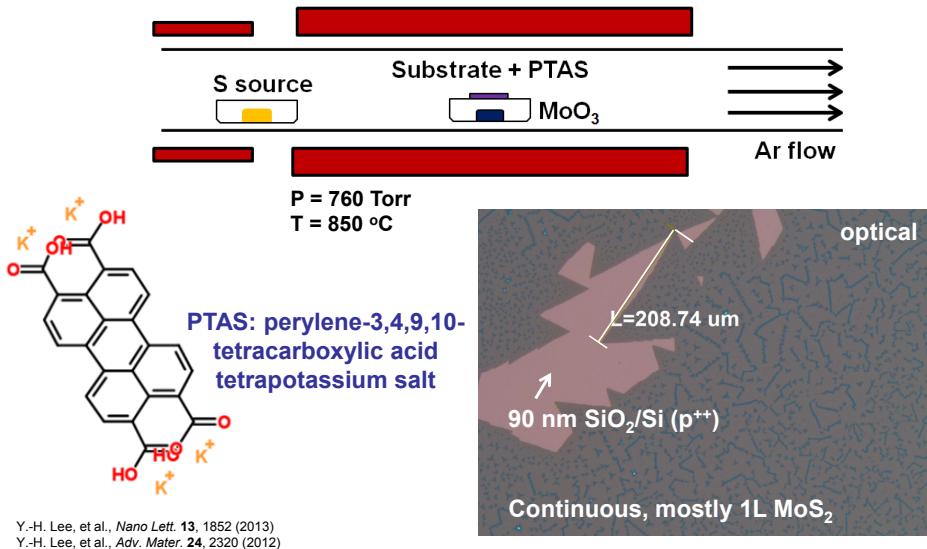
- Dot product nanofunction used for image processing, neural networks...
- Takes advantage of native graphene properties, tolerates drawbacks



## CVD Growth of Monolayer MoS<sub>2</sub>

Kirby Smith (Pop Lab)

### 2" Tube Furnace Schematic



E. Pop

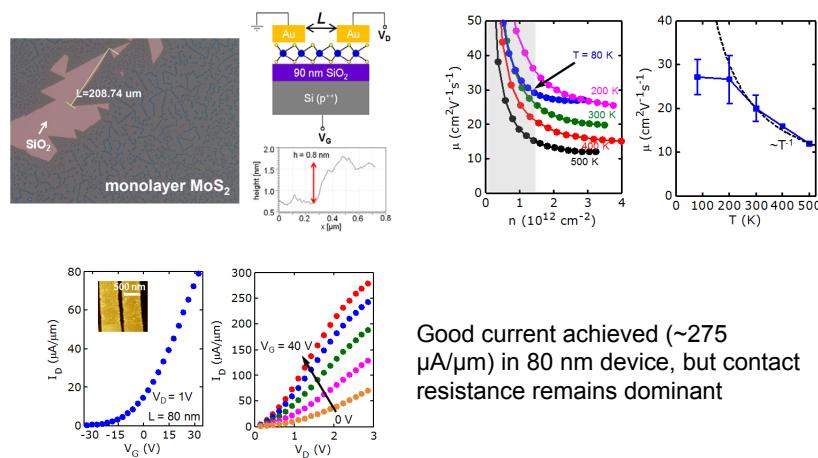
Stanford ENGINEERING

23

## Digital Electronics → Monolayer CVD MoS<sub>2</sub>

K. Smith, C. English, S. Suryavanshi, E. Pop, *Device Research Conf.* (2015)

- Large-area monolayer CVD MoS<sub>2</sub>, direct band gap ~1.8 eV
- Wish to scale up devices for low-power **digital** electronics



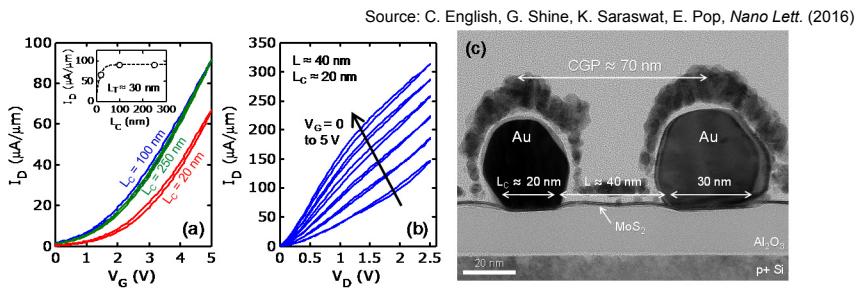
E. Pop

Stanford ENGINEERING

24

## Scaled Semiconducting MoS<sub>2</sub> Transistors

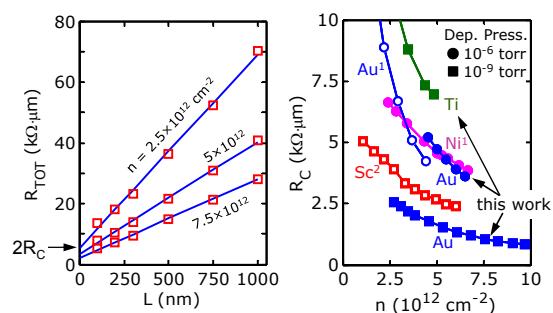
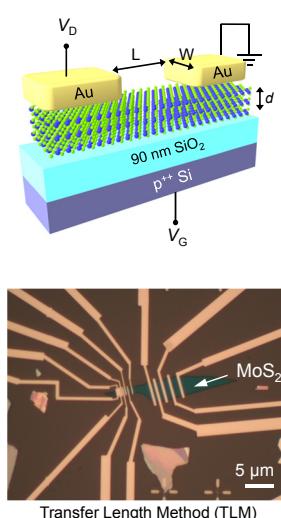
**Goal:** Aggressively scale 2D transistors (e.g. MoS<sub>2</sub>) for ultra-low power *digital* electronics



- Demonstrated how **contacts are limiting** the performance of small MoS<sub>2</sub> transistors
- Built devices with  $\sim 40$  nm channel length and variable contact sizing ( $L_C = 20$  to 100 nm)
- Smallest MoS<sub>2</sub> transistor with smallest contacts to date** (contacted gate pitch CGP  $\sim 70$  nm, smaller than "22 nm" Si technology from Intel and Samsung)

## Metal Contacts to MoS<sub>2</sub> (Clean but Undoped)

C. English, G. Shine, V. Dorgan, K. Saraswat, E. Pop, *Device Research Conf.* (2014)

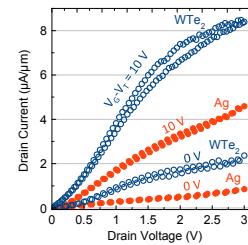
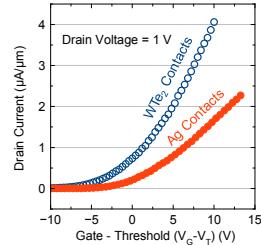
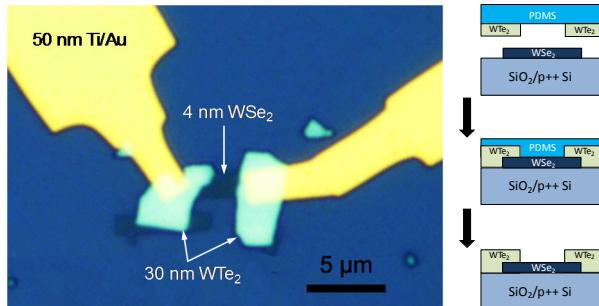


- Contacting 2D materials is **difficult**
- Cleaner Au deposition ( $\sim 10^{-9}$  torr) leads to improved contact resistance
  - $R_C \sim 740 \Omega\cdot\mu\text{m}$  and  $\rho_C \approx 4 \times 10^{-7} \Omega\cdot\text{cm}^2$

<sup>1</sup>H. Liu & P. Ye (2013), <sup>2</sup>S. Das & J. Appenzeller (2013)

## 2D Contacts to 2D Transistors

C. McClellan, M. Mleczko, Y. Nishi, E. Pop, Device Research Conf. 2016



- WTe<sub>2</sub> (2D metal) contacts to WSe<sub>2</sub> (semic.)
- Residue-free transfer process
- 2x improvement over Ag contacts ("best known")
- Observed current saturation

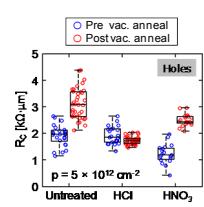
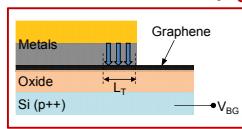
E. Pop

Stanford ENGINEERING

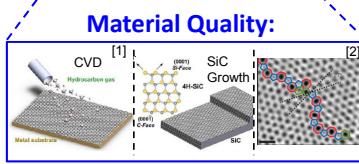
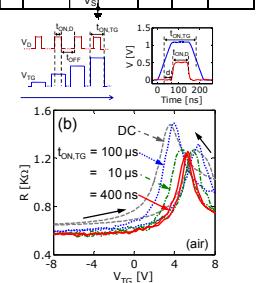
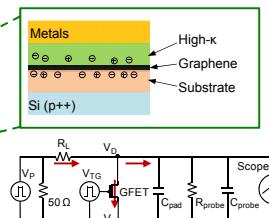
27

## Summary of Challenges in 2D Devices

### Contact Resistance ( $R_C$ ):



### Interfaces:



+Variability!

E. Carrion, E. Pop et al, IEEE TED, 61, 1583 (2014)

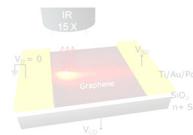
E. Pop

Stanford ENGINEERING

28

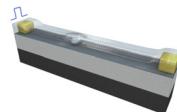
## Outline of Talk

- The SystemX Alliance at Stanford



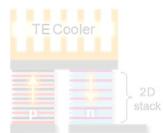
- Transistors

- Integration of electronics based on 2D materials



- Data Storage

- Approaching limits of phase-change memory

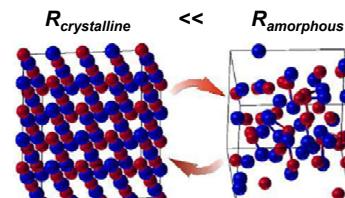


- Thermal Energy at Nanoscale

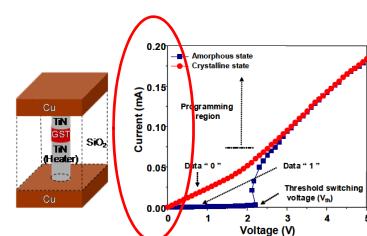
- Ballistic heat flow and fundamental limits

## Phase-Change Memory (PCM) Materials

- Chalcogenide compound:  $\text{Ge}_2\text{Sb}_2\text{Te}_5$  (GST)
- Used in RW-DVDs
- Crystalline vs. amorphous: fast phase change (~1 ns)
- Large change in resistance (>100x)
- Promising candidate for memory, BUT... high programming current (~0.1 mA at IBM, Intel, Samsung)



switching induced by Joule heating

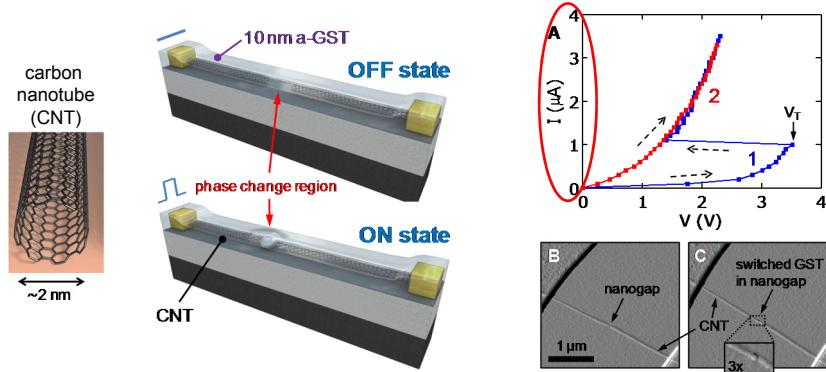


Kolobov et al. Nature Materials (2004)

Lee et al. Nature Nano (2007), Chen and Pop IEEE-TED (2009)

## Phase-Change Memory with CNT Electrodes

F. Xiong, A. Liao, D. Estrada, E. Pop, *Science* 332, 568 (2011)



- Key idea: CNTs are smallest possible electrodes (1-2 nm diameter)
- Use CNT to contact sub-10 nm bits of phase-change material
- Switching at  **$\sim 100x$  lower power** than conventional PCM!

also see. J. Liang, H.-S.P. Wong, et al., *IEEE-TED* (2012)

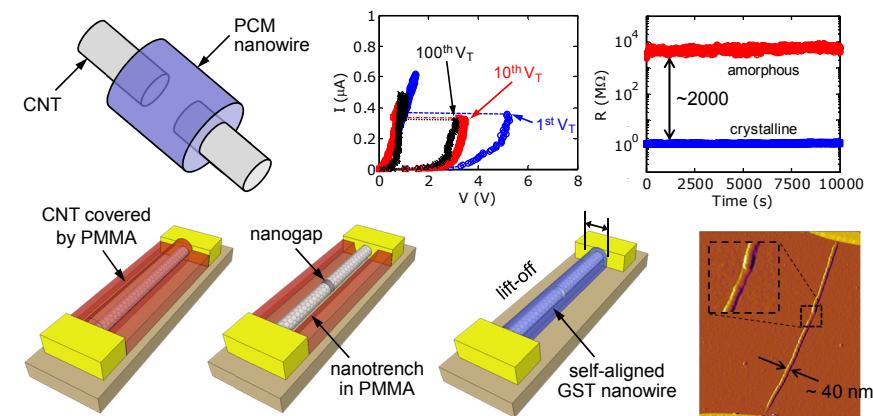
E. Pop

Stanford ENGINEERING

31

## Self-Aligned Nanotube-Nanowire Devices

F. Xiong, M.-H. Bae, Y. Dai, A. Liao, A. Behnam, E. Carrion, S. Hong, D. Ielmini, E. Pop, *Nano Lett.* 13, 464 (2013)



- “Marshmallow” memory bit optimized for **thermal confinement**
- PCM **nanowire self-aligned** with CNT electrodes
- Excellent  $R_{\text{OFF}}/R_{\text{ON}}$  ratio ( $> 1000$ ) approaches intrinsic GST limits

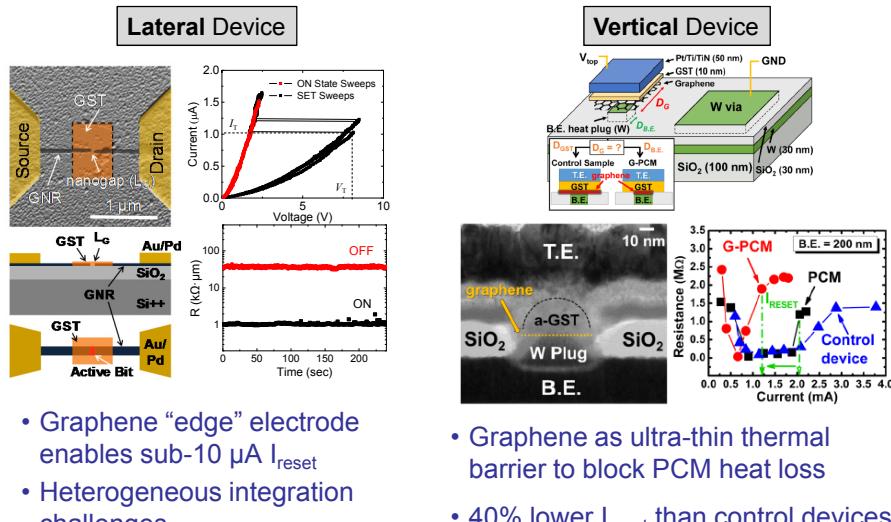
E. Pop

Stanford ENGINEERING

32

## We Can Also Use Graphene Electrodes

A. Behnam, F. Xiong, E. Pop et al., *Appl. Phys. Letters*. 107, 123508 (2015)  
 C. Ahn, S.W. Fong, Y. Kim, S. Lee, A. Sood, C. Neumann, K. Goodson, E. Pop, H.-S.P. Wong, *Nano Lett.* 15, 6809 (2015)

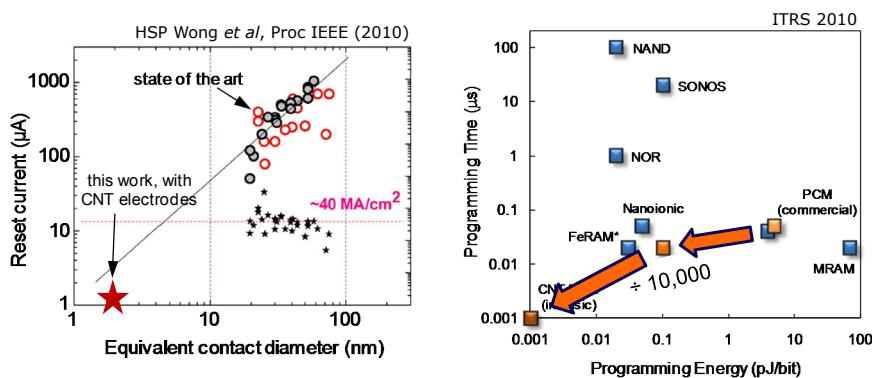


E. Pop

Stanford ENGINEERING

33

## Where These Results Fit In



\*review: S. Raoux, F. Xiong, M. Wuttig, E. Pop, *MRS Bull.* (2014)

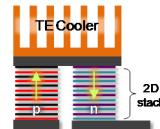
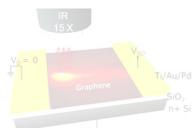
E. Pop

Stanford ENGINEERING

34

## Outline of Talk

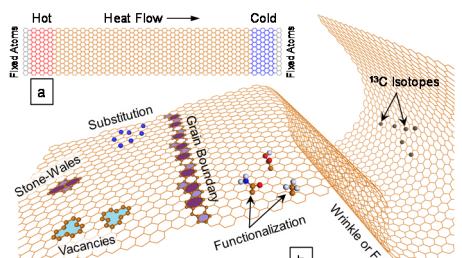
- The SystemX Alliance at Stanford
- Transistors
  - Integration of electronics based on 2D materials
- Data Storage
  - Approaching limits of phase-change memory
- Thermal Energy at Nanoscale
  - Ballistic heat flow and fundamental limits



## 2D Material Thermal Properties

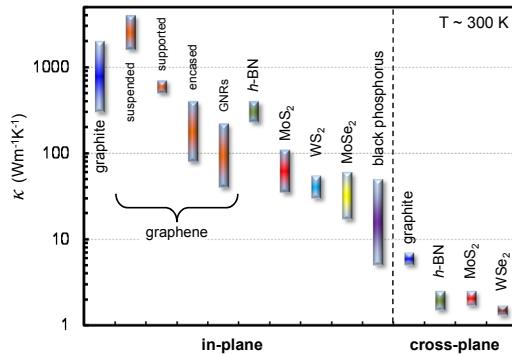
- Large in-plane thermal conductivity of graphene, BN (>500 W/m/K)
- Ultra-low cross-plane thermal conductivity of layered WSe<sub>2</sub> (<0.1 W/m/K)
  - Lower than plastics and **comparable to air**
- Huge thermal anisotropy in all layered 2D materials (>10-100x)
- MRS Bulletin review with AFRL:

E. Pop, V. Varshney, A.K. Roy, "Thermal Properties of Graphene: Fundamentals and Applications," *MRS Bulletin* **37**, 1273 (2012)



- Large thermopower in TMDs ( $S \sim 0.5$  mV/K) → Thermoelectrics?  $ZT = \frac{S^2 \sigma T}{k}$

## Thermal Conductivity ( $\kappa$ ) of 2D Materials



$$Q'' = -\kappa \nabla T$$

heat flux  
 ↑  
 T gradient  
 ↓  
 thermal conductivity

- Flexural phonon modes play important role in 2D materials
- Anisotropy:**  $\kappa_{||}$  from  $\sim 6 \text{ Wm}^{-1}\text{K}^{-1}$  (WTe<sub>2</sub>) to  $\sim 2000 \text{ Wm}^{-1}\text{K}^{-1}$  (graphene)
  - Cross-plane  $\kappa_{\perp}$  is typically very small, e.g. 1 to 6  $\text{Wm}^{-1}\text{K}^{-1}$

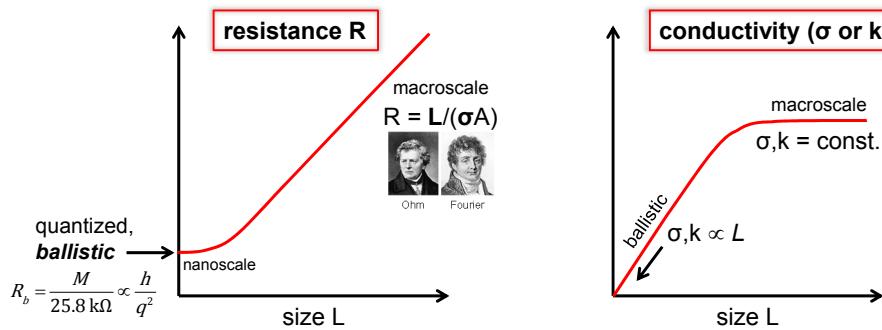
E. Pop, V. Varshney, A. Roy, *MRS Bull.* 37, 1273 (2012); Table courtesy of Z. Li (Pop Lab)

E. Pop

Stanford ENGINEERING

37

## Heat (and Current) Flow in Nanoscale Samples



- Macroscale, R is additive:  $1 + 1 = 2$
- Nanoscale**, R is quantized:  $1 + 1 = 1$ 
  - Occurs when system size is comparable to electron or phonon (heat) wavelengths and mean free path (10-100 nm)
  - Both electrical and thermal resistance can be **quasi-ballistic**

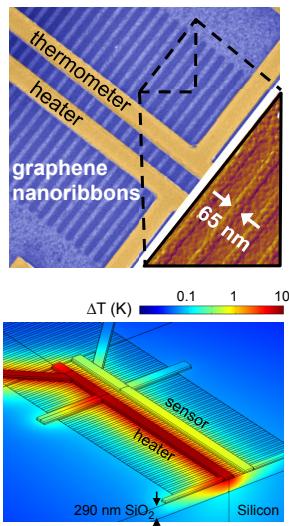
E. Pop

Stanford ENGINEERING

38

## Heat Flow in Nanoscale Graphene

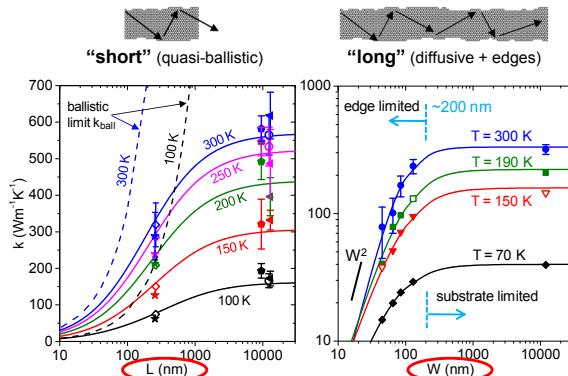
M.-H. Bae, Z. Li, Z. Aksamija, P. Martin, F. Xiong, Z.-Y. Ong, I. Knezevic, E. Pop, *Nature Comm.* 4, 1734 (2013)



**Bulk thermal properties do not apply at <1 μm!**

Thermal conductivity  $k(T) = f(W, L)$  even at room T

- 35% (quasi-)ballistic heat flow in short devices ( $\lambda \sim 100$  nm)
- Strong edge scattering in narrow devices



E. Pop

Stanford ENGINEERING

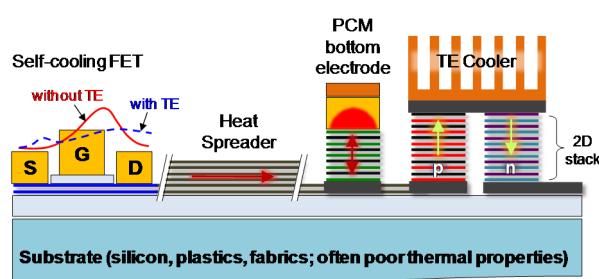
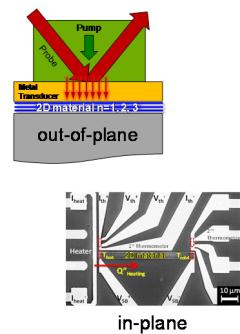
39

## Looking Ahead: Future Opportunities

collab: E. Reed, K. Goodson, K. Saraswat, H.-S.P. Wong, Y. Cui

### Could we:

- Exploit **anisotropy** for routing heat? (thermal diode)
- Separate thermal and electrical flow? (thermal transistor)
- Design electronics with **built-in thermoelectric cooling**?
- Achieve transparent heat spreaders and flexible thermoelectrics?



E. Pop

Stanford ENGINEERING

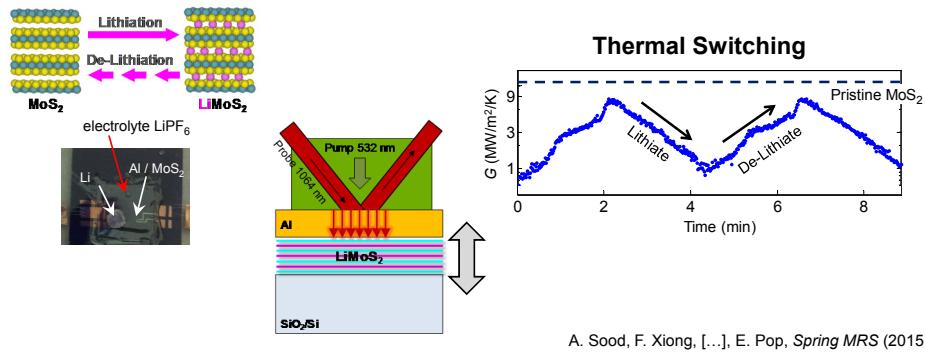
40

## Looking Ahead: Future Opportunities

collab: E. Reed, K. Goodson, K. Saraswat, H.-S.P. Wong, Y. Cui

### Could we:

- Exploit anisotropy for routing heat? (thermal diode)
- Separate thermal and electrical flow? (thermal transistor)
- Design electronics with built-in thermoelectric cooling?
- Achieve transparent heat spreaders and flexible thermoelectrics?



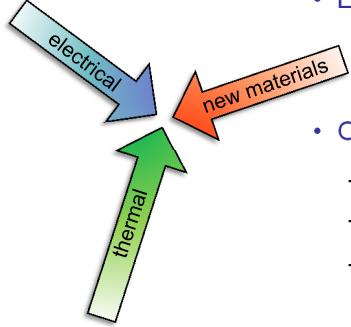
A. Sood, F. Xiong, [...], E. Pop, *Spring MRS* (2015)

E. Pop

Stanford ENGINEERING

41

## Summary



- Moore's Law ~10x → slowing down
- Energy scaling & harvesting ~10<sup>4</sup>x → exciting
- Opportunity for convergence of:
  - Novel nanomaterials
  - Low power devices
  - Anisotropy, ballistic, thermoelectric
- Understand fundamental limits
- Future opportunities

<http://poplab.stanford.edu>  
epop@stanford.edu

E. Pop

Stanford ENGINEERING

42